

Electronic Supplementary Information

Experimental section

Materials: NiCl₂·6H₂O, MnCl₂·4H₂O, NH₄F, HMT, KOH, and NaH₂PO₂ were purchased from Beijing Chemical Corp (China). Pt/C (20 wt% Pt on Vulcan XC-72R) and nafion (5 wt %) was purchased from Sigma-Aldrich. nickel foam was provided by Hongshan District, Wuhan Instrument Surgical Instruments Business. The ultrapure water used throughout all experiments through a Millipore system. All chemicals were used as received without further purification.

Preparation of hydroxide precursor : In a typical synthesis process, 3 mmol NiCl₂·6H₂O, 1 mmol MnCl₂·4H₂O, 5mmol NH₄F, 5 mmol HMT were dissolved in deionized water (30 mL) in a 50 mL beaker. After continuously stirring for 30 min, the solution was then transferred to a 50 mL Teflonlined stainless steel autoclave with a piece of nickel foam (2 cm × 3 cm). Then autoclave was sealed and maintained at 90 °C for 6 h in an oven. After the autoclave cooled down to room temperature, the hydroxide precursor was taken out and thoroughly washed with deionized water and ethanol several times alternatively, then dried at 60 °C for 6 h in air. Then the hydroxide precursor was obtained.

Preparation of Mn-Ni₂P nanosheet/NF: The hydroxide precursor was placed in an alumina boat and the other alumina boat containing 1.0 g NaH₂PO₂ was placed at the upstream of the tube furnace. The two alumina boats were calcined at 300 °C for 2 h with a heating speed of 2 °C min⁻¹ under Ar flow and then cooled down to room temperature naturally. Ni₂P/NF were made, under otherwise identical conditions, without using MnCl₂·4H₂O for hydrothermal preparation.

Characterization: The XRD patterns were obtained from a LabX XRD-6100 X-ray diffractometer with Cu K α radiation (40 kV, 30 mA) of wavelength 0.154 nm (SHIMADZU, Japan).The X-ray photoelectron spectroscopy (XPS) measurements were performed on an ESCALABMK II X-ray photoelectron spectrometer using Mg as the exciting source. The scanning electron microscopy (SEM) were collected from the tungsten lamp-equipped SU3500 scanning electron microscope at an accelerating

voltage of 20 kV (HITACHI, Japan). The transmission electron microscopy (TEM) images were obtained from a Zeiss Libra 200FE transmission electron microscope operated at 200 kV. ICP-MS analysis was performed on ThermoScientific iCAP6300.

Electrochemical measurement: The electrochemical measurements were performed on a CHI 660E electrochemical workstation (Chenhua, Shanghai). A three-electrode system was used in the experiment: a graphite rod was used as the counter electrode; a mercuric oxide electrode (Hg/HgO) was used as the reference electrode and the as-prepared Mn-Ni₂P/NF was used as the working electrode. All the measurements were performed at 298 K in 1.0 M KOH solution. The reference electrode was calibrated to the reversible hydrogen electrode (RHE): $E \text{ (RHE)} = E \text{ (Hg/HgO)} + (0.098 + 0.059 \text{ pH}) = E \text{ (Hg/HgO)} + 0.924 \text{ V}$.

TOF_{avg} calculations: The electrochemical active surface area (ECSA) is calculated using the following formula:¹

$$A_{ECSA}^{Mn-Ni_2P} = \frac{C_{dl}}{40 \text{ } \mu F \text{ } cm^{-2} \text{ per } cm^2_{ECSA}}$$

To calculate the TOF_{avg}, we used the following formula:¹

$$TOF_{avg} = \frac{\left(3.12 \times 10^{15} \times \frac{H_2/s}{cm^2} \text{ per } \frac{mA}{cm^2} \right) \times j}{2.001 \times 10^{15} \times A_{ECSA}}$$

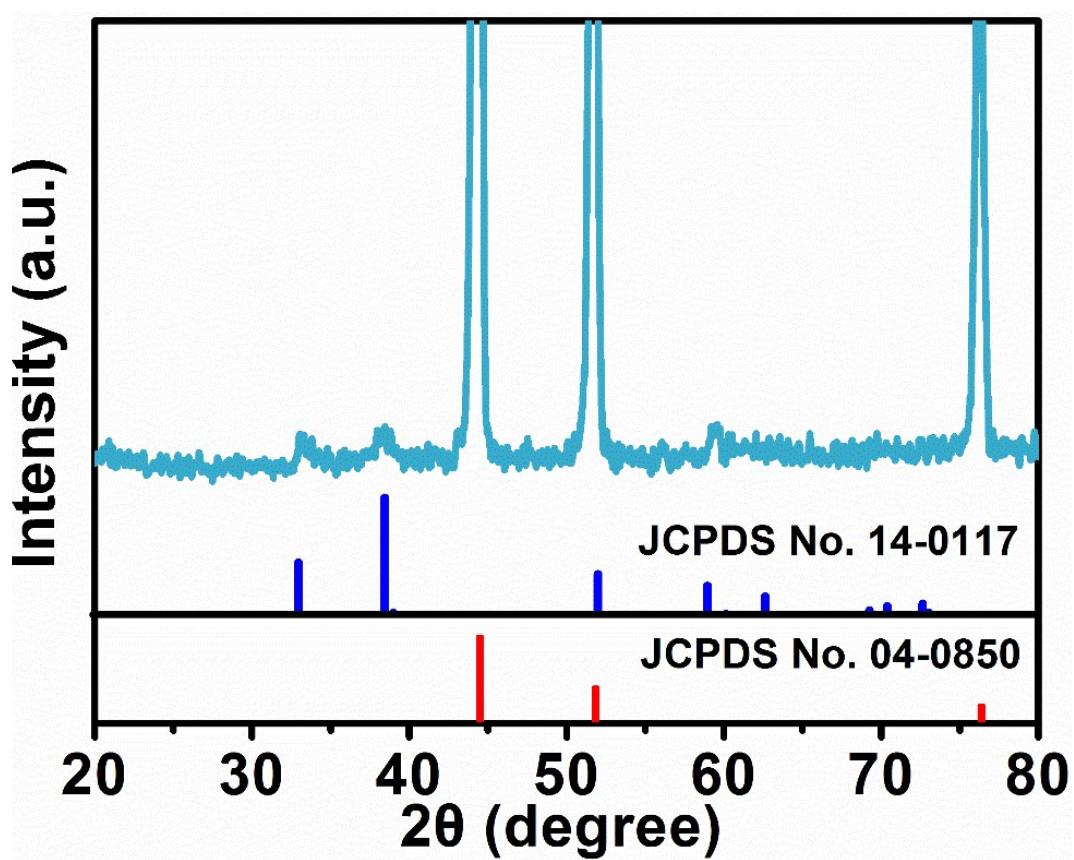


Fig. S1. XRD pattern of hydroxide precursor.

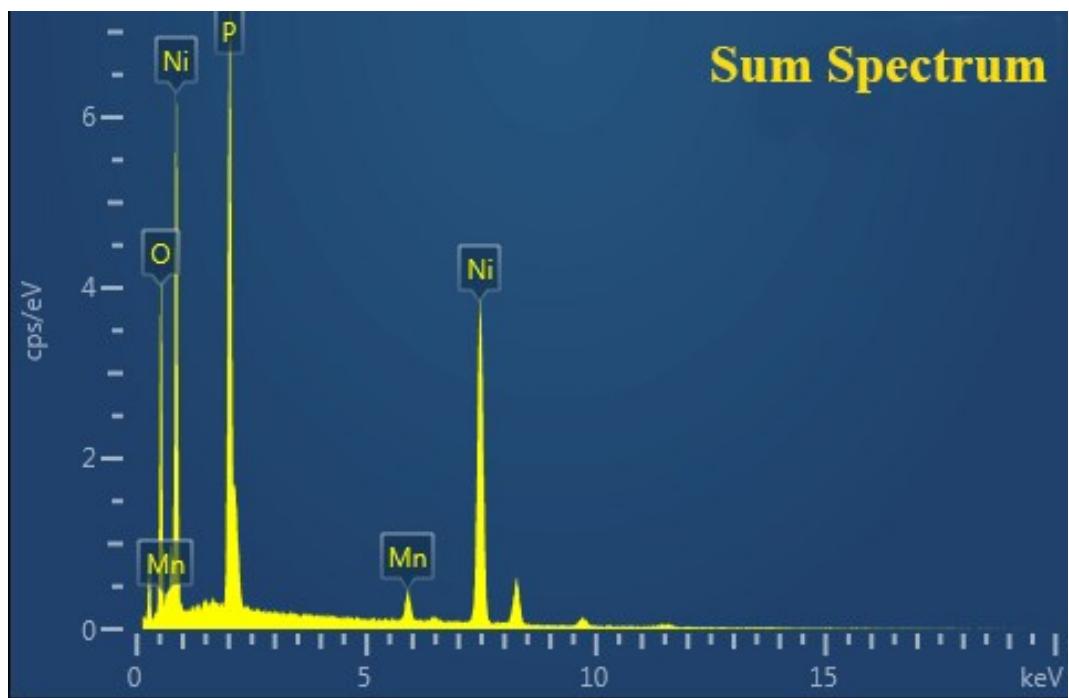


Fig. S2. EDX spectrum of Mn-Ni₂P/NF.

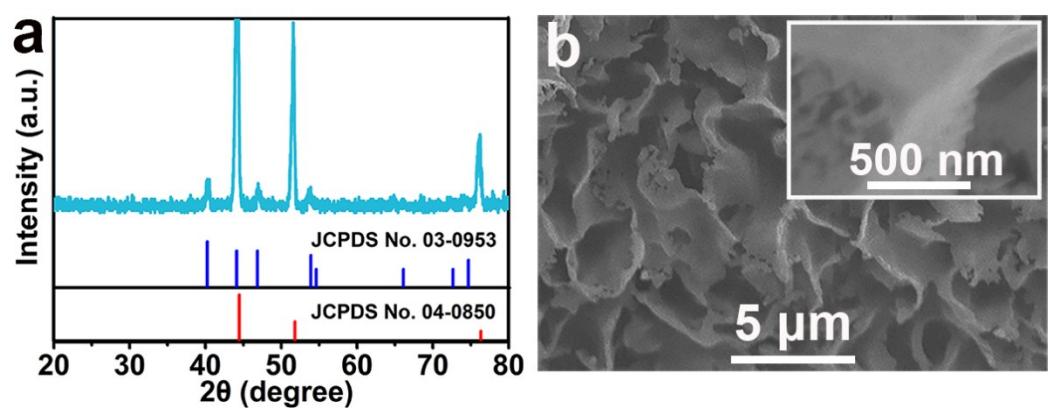


Fig. S3. (a) XRD pattern and (b) SEM images of $\text{Ni}_2\text{P}/\text{NF}$

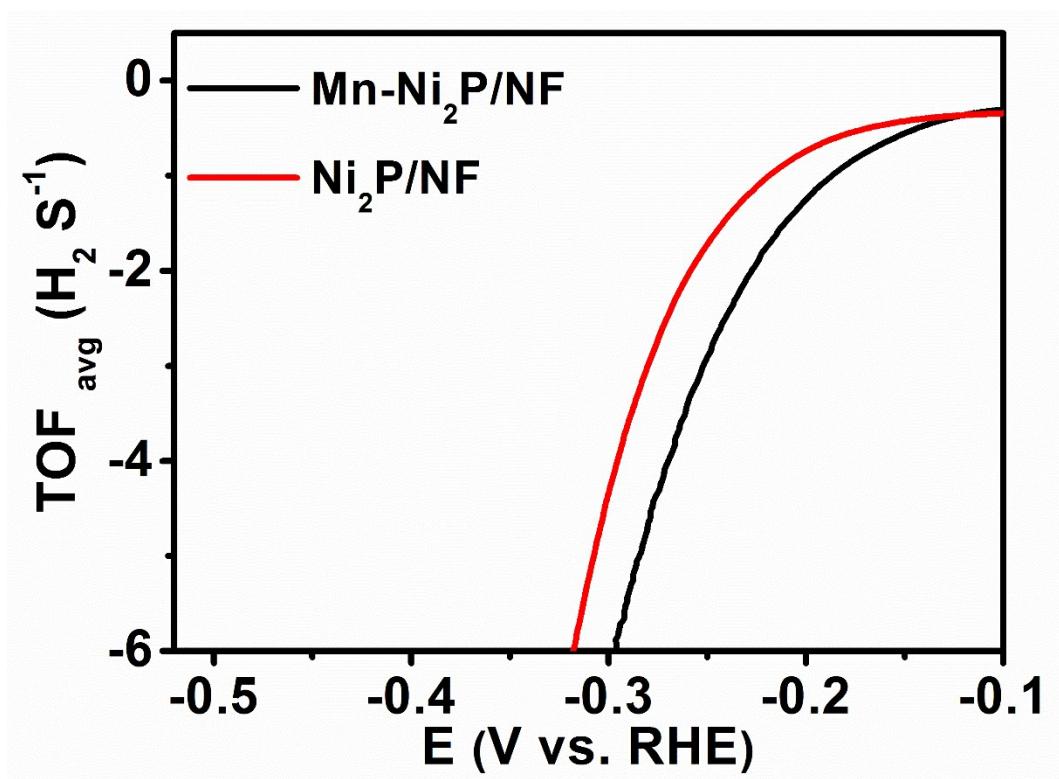


Fig. S4. TOF_{avg} calculation of Mn-Ni₂P/NF and Ni₂P/NF.

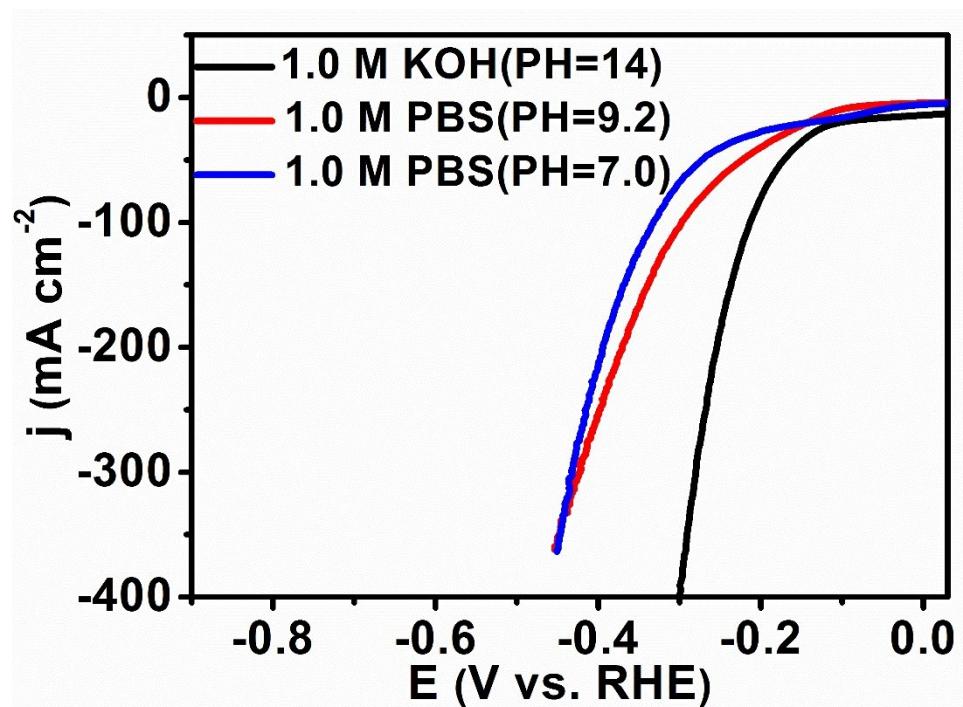


Fig. S5. LSV curves for Mn-Ni₂P/NF in pH=7.0, 9.2, 14 with a scan rate of 5 mVs^{-1} for HER with iR correction

Table S1. Comparison of HER performance for Mn-Ni₂P/NF with other non-noble-metal electrocatalysts at 1.0 M KOH

Catalyst	j (mA cm ⁻²)	η (mV)	Reference
Mn-Ni ₂ P/NF	20	103	This work
porous Ni/Ni ₃ S ₂	20	115	2
MoCx/C	20	>175	3
H ₂ -CoCat	10	>-385	4
CoOx@CN	10	270	5
MoS _{2+x} /FTO	10	310	6
CoP/CC	10	209	7
Co-NRCNTs	20	>450	8
MoB	10	>225	9
Ni ₃ N	10	208	10
NiMoN	10	109	
CoP/rGO-400	10	340	11
Ni ₃ N/NF	10	121	12
Ni wire	10	350	13
NiS ₂ /CC	10	149	14
WP ₂ submicroparticles	10	153	15
NiFe-LDH/NF	10	250	16
FeP NAs/CC	10	218	17
FeP/Fe foil	10	194	18
CFP-FeP HNA	10	181	19
Co ₂ P nanorods	20	171	20
Porous Co-P film	20	410	21
Ni ₅ P ₄ nanosheets on Ni foil	10	150	22

WP nanorods/CC	10	150	23
Ni ₂ P NSs/CC	20	250	24
Ni ₂ P/NF	15	185	25
MoP/Ni ₂ P/NF	20	110	26

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